

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/811,808	03/30/2004	Seung Wan Chae	2336-257	2845
22429 7	590 08/18/2005		EXAMINER	
LOWE HAUPTMAN GILMAN AND BERNER, LLP 1700 DIAGONAL ROAD			LOUIE, WAI SING	
SUITE 300/310		ART UNIT	PAPER NUMBER	
ALEXANDRIA, VA 22314			2814	:
			DATE MAILED: 08/18/2005	; ;

Please find below and/or attached an Office communication concerning this application or proceeding.

\sim
110
176

	Application No.	Applicant(s)				
Office Action Comme	10/811,808	CHAE ET AL.				
Office Action Summary	Examiner	Art Unit				
	Wai-Sing Louie	2814				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).						
Status						
1) Responsive to communication(s) filed on 03 June 2005.						
2a) ☐ This action is FINAL . 2b) ☑ This						
,—	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
4) ☐ Claim(s) 1-14 is/are pending in the application. 4a) Of the above claim(s) 6-14 is/are withdrawn from consideration. 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-5 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or election requirement.						
Application Papers						
9) The specification is objected to by the Examine						
10) ☐ The drawing(s) filed on is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.						
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).					
11) The oath or declaration is objected to by the Ex						
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
Attachment(s)						
1) Notice of References Cited (PTO-892)	4) Interview Summary					
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 3/04. 	Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	atent Application (PTO-152)				

DETAILED ACTION

Applicant elects Group I, claims 1-5 drawn to a GaN-based semiconductor light-emitting device with traverse. The applicant argues that there would be no serious burden in examining both groups. However, Group I is drawn to a GaN-based semiconductor light-emitting device and Group II is drawn to a method for manufacturing the device. The Inventions Group I and Group II are related as process of making and product made and the inventions Group I and Group II belong to different classes, which require separate searches and considerations. The separate searches and considerations for each group would provide a burden on the examiner. As such, the restriction is proper and the restriction is final. It is suggested that non-elected claims 6-14 be canceled in the response to this Office Action.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-5 are rejected under 35 U.S.C. 102(e) as being anticipated by Hata et al. (US 6,649,942).

Application/Control Number: 10/811,808

Art Unit: 2814

With regard to claim 1, Hata et al. disclose a nitride-based semiconductor light-emitting device (col. 6, line 1 to col. 27, line 47 and fig. 1) comprising:

- A substrate on which a GaN-based semiconductor material is grown (col. 6, line 9 and fig. 1);
- A lower clad layer 4 formed on the substrate 1, and made of a first conductive GaN material (col. 6, lines 9-12 and fig. 1);
- An active layer formed on a designated portion of the lower clad layer 4 and made
 of an undoped GaN semiconductor material (col. 6, lines 17-25 and fig. 1-2);
- An upper clad layer 7 formed on the active layer 5, and made of a second conductive GaN semiconductor material (col. 6, line 29 and fig. 1);
- An alloy layer 10a formed on the upper clad layer 7, and made of an alloy selected from the group consisting of La-based alloy and Ni-based alloy (col. 25, lines 46-61);
- A transparent conduct oxide layer 10b formed on the alloy layer 10a (col. 26, lines 1-10 and fig. 1).

With regard to claim 2, Hata et al. disclose the thickness of the alloy layer 10a is 2 nm (col. 6, lines 51-52).

With regard to claim 3, Hata et al. disclose the La-based alloy is LaNi₅ (col. 25, line 53). With regard to claim 4, Hata et al. disclose the Ni-based alloy is MgNi (col. 25, line 52). With regard to claim 5, the transparent conduct oxide layer 10b is ITO (col. 26, line 9).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Wai-Sing Louie whose telephone number is (571) 272-1709. The examiner can normally be reached on 7:30 AM to 4:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (571) 272-1705. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

August 11, 2005.